



Form 1449 (Modified)

**Information Disclosure  
Statement By Applicant**

(Use Several Sheets if Necessary)

Atty Docket No.  
**LAM1P177/P1139**

Applicant:  
**KANG et al.**

Filing Date  
**August 26, 2003**

Application No.:  
**10/648,953**

Group  
**2811**

**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub- class	Filing Date
	A1.						
	A2.						
	A3.						
	A4.						
	A5.						
	A6.						
	A7.						
	A8.						
	A9.						
	A10.						

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub- class	Translation	
							Yes	No
	B1.							
	B2.							
	B3.							
	B4.							
	B5.							

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1.	U.S. Application No. 11/016,455, entitled "Reduction of Etch Mask Feature Critical Dimensions", by inventors Huang et al., filed 12/16/04.
	C2.	U.S. Application No. 11/208,098, entitled "Etch Features with Reduced Line Edge Roughness", by inventors Sadjadi et al., filed 08/18/05.
	C3.	
	C4.	

Examiner	Date Considered
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Examiner. Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.